



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Kiyoichi SUWA

Group Art Unit: 2818

Application No.: 09/729,339

Examiner: Q. D. Hoang

Filed: December 5, 2000

Docket No.: 108057

For: MASK, EXPOSURE METHOD, LINE WIDTH MEASURING METHOD, AND
METHOD FOR MANUFACTURING SEMICONDUCTOR DEVICES

15/11 to.
G. Staley
11-18-02
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CONFIRMATION OF TELEPHONE INTERVIEW

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

Applicant thanks Examiner Hoang for the courtesies extended to Applicant's representative during the October 29, 2002 telephone interview. Applicant further appreciates Examiner Hoang agreeing to withdraw the finality of claims 2-4 and 12-14 in the September 16, 2002 Final Rejection as Examiner Hoang agreed that the Office Action should not have been made final. Accordingly, the finality of the Office Action has been withdrawn. Examiner Hoang stated that in the near future he would issue a new Non-Final Office Action. Applicant looks forward to receipt of the Non-Final Office Action with a new time period for response.

Should the Examiner desire to contact Applicant's representative, the Examiner is invited to contact Applicant's undersigned representative at the telephone number listed below.

Respectfully submitted,

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MAC:RZE/dmw
Date: October 30, 2002

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